

## IN THE CLAIMS

1.-11. (Cancelled).

12. (Currently Amended) An electron beam exposure apparatus comprising:

an electron gun which emits an electron beam;

a mask stage on which an electron beam exposure mask for intercepting part of said electron beam is placed, said electron beam exposure mask including

a main mask having a plurality of first defined masks, and

one or more compensation masks including one or more non-defective second defined masks each having a pattern configuration to be ~~formed in~~ used instead of a defective first defined mask among said plurality of first defined masks;

a wafer stage on which a wafer provided with an electron beam resist film is placed;

a first electron beam optical system which projects said electron beam onto said electron beam exposure mask;

a second electron beam optical system which projects said electron past said electron beam exposure mask onto said electron beam resist film;

a storage device which stores the address of a defective first defined mask among said plurality of first defined masks and the address of a second defined mask ~~corresponding to~~ having a pattern configuration to be used instead of said defective first defined mask; and

a control device which controls the deflection of said electron beam in said first and second electron beam optical systems, said control device, when the address of said defective first defined mask is designated, replacing it with the address of said second defined mask ~~corresponding to~~ having a pattern configuration to be used instead of said defective first defined mask.